Programming Strategy

- First determine **GSel** based on the desired approximate transfer gain (approx. 50 200 mV/fC).
- Then depending on the value of the input capacitance (Cin), program **BWSel** to achieve fast integrator response without ringing.
- For Cin = 2 pF (1.5 pF detector + 0.5 pF parasitic):

 If GSel = 000, set BWSel = 00000

 If GSel = 010, set BWSel = 00100

 If GSel = 100, set BWSel = 01000

 If GSel = 110, set BWSel = 01100

Physics	Dec	Bin
GSel	2	010
BWSel	4	1000

Relevant setting for INTT if the strip capacitance is > 2pF

- For Cin = 1.5 pF (1 pF detector + 0.5 pF parasitic):
 - If GSel = 000, set BWSel = 00001
 - If GSel = 010, set BWSel = 00110
 - If GSel = 100, set BWSel = 01010
 - If GSel = 110, set BWSel = 01110

•	For	Cin = 1 pF (0.5 pF detector $+$ 0.5 pF parasitic):
		If $GSel = 000$, set $BWSel = 00010$
	_	If $\mathbf{GSel} = 010$, set $\mathbf{BWSel} = 01000$
	_ '	If $GSel = 100$, set $BWSel = 01110$
	_	If $GSel = 110$, set $BWSel = 10101$

	Nevis	Dec	Bin
•	GSel	2	010
	BWSel	8	1000

Relevant setting for INTT if the strip capacitance is ~ 0.5pF

- Program **Fb1Sel** based on the desired fall time constant
- Then program **N2Sel** to achieve the desired rise time/peaking time (rise and fall times will have some effect on the transfer gain)
- Program **Vref** to the lowest value possible that allows linear response (nominally 00)
- Based on the transfer gain, set the desired comparator thresholds

Strip Capacitance

The strip length increases with radius on the sensor, and goes from 3.4 mm at the inner radius to 11.5 mm at the outer radius, with a pitch of 75 μ m in the radial direction. Each sensor covers 7.5° in ϕ , and since the strips are perpendicular to the radius, they make an angle of 86.25° with respect to the centerline, as can be seen in Fig. 4.

The data words are output over two LVDS serial lines at up to 200 MHz clock rate. The total power consumption of the FPHX is $\sim\!390~\mu\text{W}$ per channel. The noise, when the chip was wire bonded to a sensor with strips $\sim\!2\text{--}11~\text{mm}$ in length ($\sim\!1\text{--}2.5~\text{pF}$), was simulated and measured to be below the design specification of 500 electrons.

There are discrepancy between the actual measurement by Kaiyu, Hamamatsu, and expected value by simple scaling from FPHX by the length of the strip.



Strip	Thickness [μm]	Width [μm]	Length [mm]	Capacitance [pF]	Measurement (Kai-Yu)	Hamamatsu
FVTX	320	78	2 ~ 11 mm	1 ~ 2.5		
INTT-Type-A			12mm	2.5*	~ 1 [pF]	0.64 [pF]
INTT-Type-B			18mm	3*		

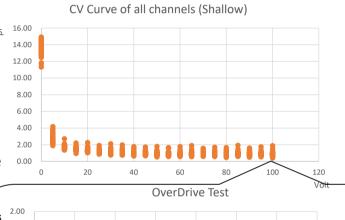
Kai-Yu's Capacitance Measurement

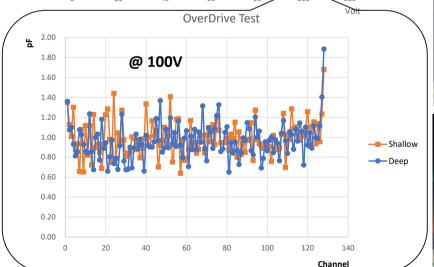
Trace Test (in Bad Sensor)

~1pF

 Is this measurement pure capacitance off the silicon?

Don't know if the effect of readout line

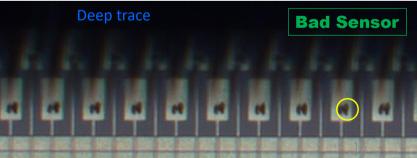




INTT_CV_System_BiWeekMeeting_200422.pdf







Compare Result

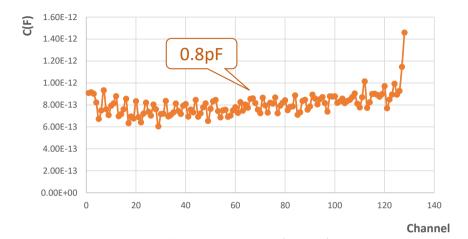
- Compare the result between single channel, one chip and HAMAMATSU inspection.
- My result come from the bad sensor, so the sensor is different with HAMAMATSU inspection
- The ratio between single channel and one chip is correct.

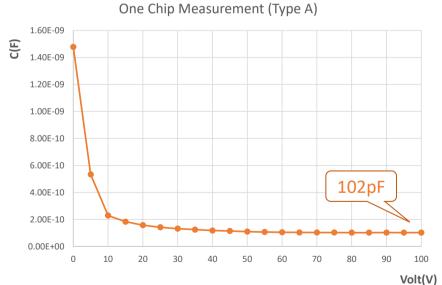
Single channel: 0.8pF @100V **Bad Sensor** One Chip: 0.8 * 128 = 102.4102pF @100V

Full sensor(expect): 1632pF @100V

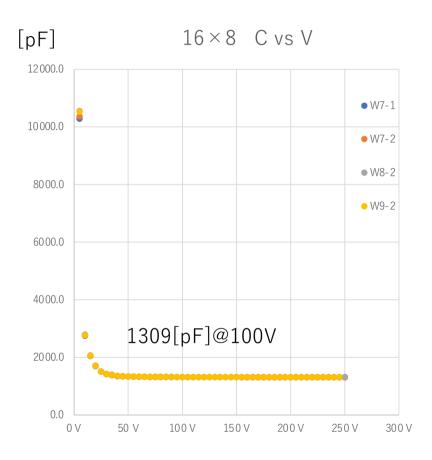
HAMAMATSU(full sensor): 930pF @100V

2020/5/6





Hamamatsu's Measurement



$$\frac{1309 [pF]total}{128 [strip] 16 [cell]} = 0.639 [pF/strip]$$